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(54) Title (EN): CONTACT BLOCK ARRANGED AT THE FREE END OF AN ELECTRODE SUPPORT ARM FORMING A COMPONENT OF AN ELECTRIC OVEN

(54) Title (FR): CUILLERE DE CONTACT DISPOSEE DE MANIERE AMOVIBLE A L'EXTREMITE LIBRE D'UN BRAS PORTE-ELECTRODE QUI FORME UNE PARTIE D'UN FOUR ELECTRIQUE

(54) Title (DE): AM FREIEN ENDE EINES BESTANDTEIL EINES ELEKTROOFENS BILDENDEN ELEKTRODENTRAGARMS AUSWECHSELBAR ANGEORDNETE KONTAKTBACKE

(57) Abstract:

(EN): The aim of the invention is the reduction of the impairment in current transfer from the contact plate (112), forming part of the electrode support arm (11), to the contact block (12), interacting with the electrode, caused by deposits between the contact plate (112) and the contact block (12) due to erosion during the fusion operation. Said aim is achieved, whereby the contact block (12) which may be brought into planar contact against a partial region of the electrode (21), is provided with a medial passage (124), running to the support arm (11), for removal of at least the large part of the erosion, said passage having a continuation (111) in the support arm (11).

(FR): L'objectif de cette invention est de réduire les effets négatifs de la transition de courant de la plaque porte-contact (112) qui forme une partie du bras porte-électrode (11), sur la cuillère de contact (12) qui coopère avec l'électrode, en raison de dépôts entre la plaque porte-contact (112) et la cuillère de contact (12) qui sont dus à l'usure pendant le processus de fusion. A cet effet, la cuillère de contact (12) qui peut être disposée de manière plane contre une zone partielle de l'électrode (21) comporte un passage (124) central qui s'étend vers le bras support (11) pour évacuer au moins la majeure partie du dépôt et qui se prolonge (111) dans le bras de support (11).

(DE): Mit dem Ziel, die Beeinträchtigung des Stromübergangs von der Bestandteil des Elektrodentragarms (11) bildenden Kontaktplatte (112) auf die mit der Elektrode in Wechselwirkung tretende Kontaktbacke (12) durch auf Abbrand während des Schmelzbetriebes hervorgerufene Ablagerungen zwischen Kontaktplatte (112) und Kontaktbacke (12) zu reduzieren, wird die gegen einen Teilbereich der Elektrode (21) flächig zur Anlage bringbare Kontaktbacke (12) zwecks Abführung zum mindest des grössten Teils des Abbrandes mittig mit einem zum Tragarm (11) hin auslaufenden Durchgang (124) versehen, der im Tragarm (11) seine Fortsetzung findet (111).

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